

STN 3 USPAT

(FILE 'HOME' ENTERED AT 14:44:56 ON 19 AUG 2002)

FILE 'USPATFULL' ENTERED AT 14:45:01 ON 19 AUG 2002

L1 604883 S CARBON OR GRAPHITE OR C-C OR CARBON-CARBON
L2 304082 S RESIST# OR PHOTORESIST# OR MASK# OR PHOTOMASK#
L3 1921838 S ETCH? OR PATEEN? OR PATTERN? OR REMOV?
L4 43627 S L1(10A)L3
L5 1240 S L2(10A)L4
L6 558 S L5 NOT (SEMICONDUCT? OR WAFER# OR CHIP#)
L7 420559 S O2 OR O3 OR OXYGEN? OR O(W)SUB(W)2 OR O(W)SUB(W)3
L8 1116352 S AL OF ALUMINUM? OR ALCU OR ALSI OR ALCUSI OR ALSICU OR SILICO
L9 41094 S L5(10A)L2
L10 472 S L5(P)L7
L11 290 S L5(P)L9
L12 607 S L10 OR L11
L13 54 S L5 AND L12
L14 144 S L5(P) CARBON(W) DIOXIDE OR CARBON(W)MONOXIDE)
L15 31 S L13 NOT L14
L16 571 S L12 NOT L13
L17 45 S L16 AND (FUEL(3A)CELL? OR HEAT?(3A)EXCHANG?)
L18 9 S L16 AND (FIN OR FINS)
L19 52 S L17 OR L18
SET HIGH OFF
L20 52 S L19
SET HIGH ON
L21 52 S L16 AND L20
L22 18 S L13 NOT L15
L23 6 S L21 NOT (CARBON(W) (TETRAFLUORID? OR FLUORID? OR MONOXIDE? OR
L24 1138 S L5 NOT (L13 OR L21)
L25 375 S L5(P) (CARBON(W) (TETRAFLUORID? OR FLUCRID? OR MONOXIDE? OR DIC
L26 2 S L21 NOT (L23 OR L25)
L27 293 S L5(P) (SEMICONDUCT? OR WAFER# OR CHIP#)
L28 581 S L5 AND (SEMICONDUCT? OR WAFER# OR CHIP#)/TI,AB,CLM
L29 588 S L5 NOT (L27 OR L28)
L30 529 S L24 AND L29
L31 157 S L30 AND CARBON OR GRAPHITE OR C)/TI,AB
DEL ELECTRONL27/A
DEL ELECTRONL28/A
DEL ELECTRONL29/A
SAVE ETCHL31,A L31

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STN 2 Cds Tape

(FILE 'HOME' ENTERED AT 09:54:35 ON 19 AUG 2002)

FILE 'CA' ENTERED AT 09:54:32 ON 19 AUG 2002

L1 1000341 S CARBON OR GRAPHITE?
L2 1559842 S ETCH? OF PATTERN? OR PATTERN? OF REMOV?
L3 103020 S RESIST# OR PHOTORESIST# OR MASK# OR PHOTOMASK#
L4 1163841 S AL OF ALUMINUM?
L5 1360719 S SI OF SILICON OF POLY OR POLYSI?
L6 620253 S OXIDATION OR OXIDIZ?
L7 36046 S L11 AND L2
L8 19477 S L11 AND L4 OR L5
L9 54 S L1 AND L3
L10 20 S L11 AND RESIST OR PHOTORESIST?
L11 12 S L10 AND L8
L12 47 S L9 AND L5
L13 2 S L12 AND (CARBON OR GRAPHITE OR C)/TI
L14 1 S L12 AND GRAPHITE?/AB
L15 1 S L14 NOT L13
L16 44 S L12 NOT (L13 OR L14)
L17 10 S L16 AND (ETCH? OF PATTERN? OR PATTERN? OR REMOV?)/TI
L18 34 S L16 NOT L17
L19 105 S (L9 OR L19) AND (CARBON OR GRAPHITE OR C)/TI
L20 101 S L19 NOT (L11 OR L12)
L21 66 S L20 AND (ETCH? OF PATTERN? OR PATTERN? OR REMOV?)/TI
L22 41658 S C(10A)L2
L23 911 S L22(10A)L3
L24 504 S L22 AND L8
L25 1179 S L23 OR L24
L26 1096 S L25 NOT L9 OR L10)
L27 76 S L6 AND L26
L28 34 S L26 AND (CARBON OR GRAPHITE OR C)/TI
L29 12 S L27 AND (ETCH? OF PATTERN? OR PATTERN? OR REMOV?)/TI
L30 1 S L28 AND L29
L31 61 S L28 NOT L30
L32 73 S L27 NOT L30 OR L31)
L33 75 S L32 OR L29
SET HIGH OFF
L34 75 S L33
SET HIGH ON
L35 75 S L34 AND (CARBON OR GRAPHITE OR C)
L36 762 S L9 OR L10
L37 1859 S L26 OR L36

FILE 'JAPIO' ENTERED AT 10:20:30 ON 19 AUG 2002

L38 1389 S L37
L39 308 S L38 AND (CARBON OR GRAPHITE)
SET HIGH OFF
L40 10 S L39
L41 141 S L39 NOT L40
SET HIGH ON
L42 10 S L41 AND GRAPHITE
L43 1 S L42
L44 144 S L41 AND CARBON
L45 63 S L44 AND (CARBON OR FILM? OF LAYER?)
L46 232 S L44 NOT L45
L47 63 S L46 AND L45

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STN 2 Cas Japio

FILE 'CA' ENTERED AT 15:26:15 ON 19 AUG 2002)

TEL HIF

L1 62555 S CARBON W CARBON OR CARBON-CARBON OR C-C
L2 1559-49 S ETCH? OF PATTERN? OR REMOV? OF PATTERN?
L3 103020 S MASK# OR PHOTOMASK# OR RESIST# OR PHOTORESIST#
L4 3 S L1(10A)L2(10A)L3
L5 13584 S CARBON(W)CARBON OR CARBON-CARBON
L6 0 S L5(10A)L2(10A)L3
L7 14 S L5 AND L2 AND L3
L8 53132 S C-C
L9 1456 S L8(W)COMPOSIT?
L10 0 S L2(10A)L3(10A)L9
L11 17 S L7 OF L10 OR L4

FILE 'JAPIO' ENTERED AT 15:29:56 ON 19 AUG 2002

L12 27 S L11

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